The 38th International Conference of Photopolymer Science and Technology (ICPST-38)

Materials & Processes for Advanced Lithography, Nanotechnology and Phototechnology

http://www.spst-photopolymer.org

Online Conference

June 15 - 16, 2021

The International Conference of Photopolymer Science and Technology (ICPST) organized by the Society of Photopolymer Science and Technology (SPST) for these 38 years has played an important role as a world-wide forum for discussion and information exchange on the resist material process technology used in various lithographic technologies such as g-line, i-line, KrF, ArF, electron beam, and X-ray. ArF immersion lithography is currently used for 22-nm-generation semiconductor manufacturing technology. In 2019, EUV lithography has started to be used in HVM of 7-nm-node-logic devices for smart phones. And EUV lithography, nanoimprint lithography, and DSA technology are promising candidates for semiconductor nano-fabrication technologies in next 5 nm node and beyond. At the International Electron Devices Meeting (IEDM) 2019, several chip manufacturers reported that advanced lithography is required in the future for the mass production of semiconductor devices continuously For supporting the future IoT technology, advanced techniques of the lithography are required increasingly, where material technologies such as photo-functional groups, photo-acid generators, photo-curable resins, etc. are the driving force for the progress of semiconductor technology with quantum scale and quantum effect. Basic research on photopolymer is more significant in developing new technologies such as quantum device technology with lower power consumption and lower manufacturing cost by combining with life science and quantum device technology. New Symposia will continue to be provided in place of conventional ones. The international symposium of Organic Solar Cells – Materials, Device Physics, and Processes was added in 2017. In addition, the international symposium of Fundamentals and Applications of Biomimetics Materials and Processes was added in 2018. In addition, the plenary session will be held to introduce the promising and significant technology in the future related on photopolymer science and technology. In ICPST-38, Dr. Yasumitsu Orii, the Executive Officer of New Value Creation Office and the General Manager of NAGASE will present the plenary talk of **"Development of Materials Informatics Platform".** Constructive opinions from researchers and scientists are welcomed for future progress of ICPST.

English Symposia

- **A0. Plenary Talk**
- **A1. Next Generation Lithography, EB Lithography and Nanotechnology**
- **A2. Nanobiotechnology**
- **A3. Directed Self Assembly (DSA)**
- **A4. Computational / Analytical Approach for Lithography Processes**
- **A5. EUV Lithography**
- **A6. Nanoimprint Lithography**
- **A7. 193 nm Lithography Extension and EUV HVM Readiness**
- **A8. Photopolymers in 3-D Printing/ Additive Manufacturing**
- **A9. 2D and Stimuli Responsive Materials for Electronics & Photonics**
- **A10. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices**
- **A11. Chemistry for Advanced Photopolymer Science**
- **A12. Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices**
- **A13. Fundamentals and Applications of Biomimetics Materials and Processes**
- **A14. General Scopes of Photopolymer Science and Technology**
- **P1. Panel Symposium I "EUV Lithography toward 10 nm and below – Prospect of Achievement for Both Highly Sensitive and low LWR EUV Resist "**
- **P2. Panel Symposium II "Biomimetics: Learn from Nature"**

Japanese Symposia

- **B1. Polyimides and High Temperature Polymers -Functionalization and Practical Applications-**
- **B2. General Scopes of Photopolymer Science and Technology**

NOTICE: All by Online Conference

All symposia will run by online conference.

1) **Opening session, Plenary talk, and Two Panel Symposium will run by Live online conference by ZOOM.**
2) **All symposia except Panel Symposium will run by on demand streaming.**

Schedule *(tentative)*

1) Live online conference using ZOOM June 15 and 16, 2021

June 15	June 16
Opening Session (21:00 - 21:10)	Panel Symposium II (21:30 - 23:30)
Plenary Talk (21:10 – 21:55)	
Panel Symposium I (21:55 – 23:30)	

2) On demand streaming Period: June 15 – July 14, 2021 (Total one month)

Registration (https://www.spst-photopolymer.org/conference/registration/)

Category	Early bird (until May 25, 2021)	Late and on-site (until June 16, 2021)
Government, academia and industries	35,000 JPY Journal of Photopolymer Science and Technology, Vol. 34 (2021) will be delivered before June 15th.	35,000 JPY Journal of Photopolymer Science and Technology, Vol. 34 (2021) will be delivered after June 16th.
Students	10,000 JPY	10,000 JPY

Papers (https://www.spst-photopolymer.org/journal/)

Papers submitted to ICPST-38 are published in Journal of Photopolymer Science and Technology, Vol. 34, No. 1-6 (2021). Please submit your manuscript before April 1, 2021 from the URL.

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